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Ruth Montalvo

/ Ruth Montalvo Date: 01/20/04

Customer No. 026418

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Docket No. GK-OEH-171 / 500814.20073

Applicant(s): Max Christian SCHUERMANN, et al.

Application No.: 10/672,110

Filed: September 26, 2003

Group: 2878

For: ARRANGEMENT FOR DETERMINING THE SPECTRAL
REFLECTIVITY OF A MEASUREMENT OBJECT

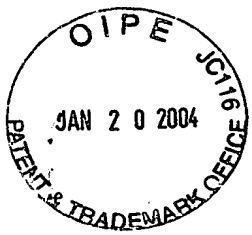
Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

S I R:

Applicant herewith submits this Information Disclosure Statement in accordance with the provisions of 37 C.F.R. §§ 1.97 and 1.98 and hereby makes of record the following references listed below:

	Document Number	Date	Name and/or Country
AT	XP-001111378 / Research Disclosure, July 2001, 1146 (2 sided page) 447085 "Reflectometer for EUV lithography components"		
AU	Microelectronic Engineering 61-62 (2002) pages 145-155, "Characterization of optics and masks for the EUV lithography" Valérie Paret, et al.		
AV	11C-2-1, "Development of EUV reflectometer using a laser-plasma x-ray source Hiroyuki Kondo, et al. (1 page/34)		
AW	XP-0010183524 / Journal of x-ray Science and Technology 3, (1992) pages 283-299, "A Soft X-Ray/EUV Reflectometer Based in a Laser Produced Plasma Source, E. M. Gullikson, et al.		
AX	XP-000497187 / 8257b Journal of Vacuum Science & Technology B 12(1994) Nov/Dec, No. New York, NY, US, pages 3826-3832, "Multilayer facilities required for extreme-ultraviolet lithography, D.L. Windt, et al.		
AY	Nuclear Instruments and Methods in Physics Research A 359 (1995) pages 151-154, Synchrotron radiation soft X-ray reflectometer and its physics results, Cui Mingqi, et al.		
AZ	XP-000920796 / Applied Optics, March 1998, Vol. 37, No. 7, pages 1243-1248, "Laser-produced lithium plasma as a narrow-band extended ultraviolet radiation source for photoelectron spectroscopy", G. Schriever, et al.		



Accompanying this Information Disclosure Statement and form PTO-1449 are copies of the seven (7) articles.

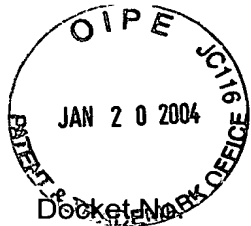
This submission is not an admission that the information disclosed in the documents is material to the patentability of the invention disclosed and/or claimed in the above-identified application.

01/20/04
GHK:ram

Tel. (212) 521-5400
Enclosures:
PTO-1449
7 Articles

Respectfully submitted,

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**Second LIST OF PRIOR ART CITED BY APPLICANT**
(Filed on January 20, 2004)

Docket No.

GK-OEH-171 / 500814.20073

Applicant(s): **Max Christian SCHUERMANN, et al.**Application No. **10/672,110**Group: **2878**Filed: **September 26, 2003**

Examiner:

U.S. PATENT DOCUMENTS

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES NO
	AL						
	AM						
	AN						
	AO						
	AP						

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AT	XP-001111378 / Research Disclosure, July 2001, 1146 (2 sided page) 447085 "Reflectometer for EUV lithography components"
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